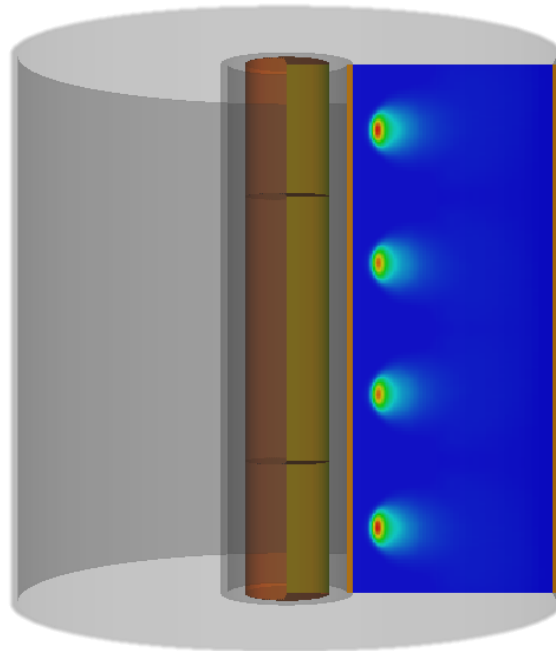


— CASE EXAMPLE —

# Magnetron Sputtering for Cylindrical Target

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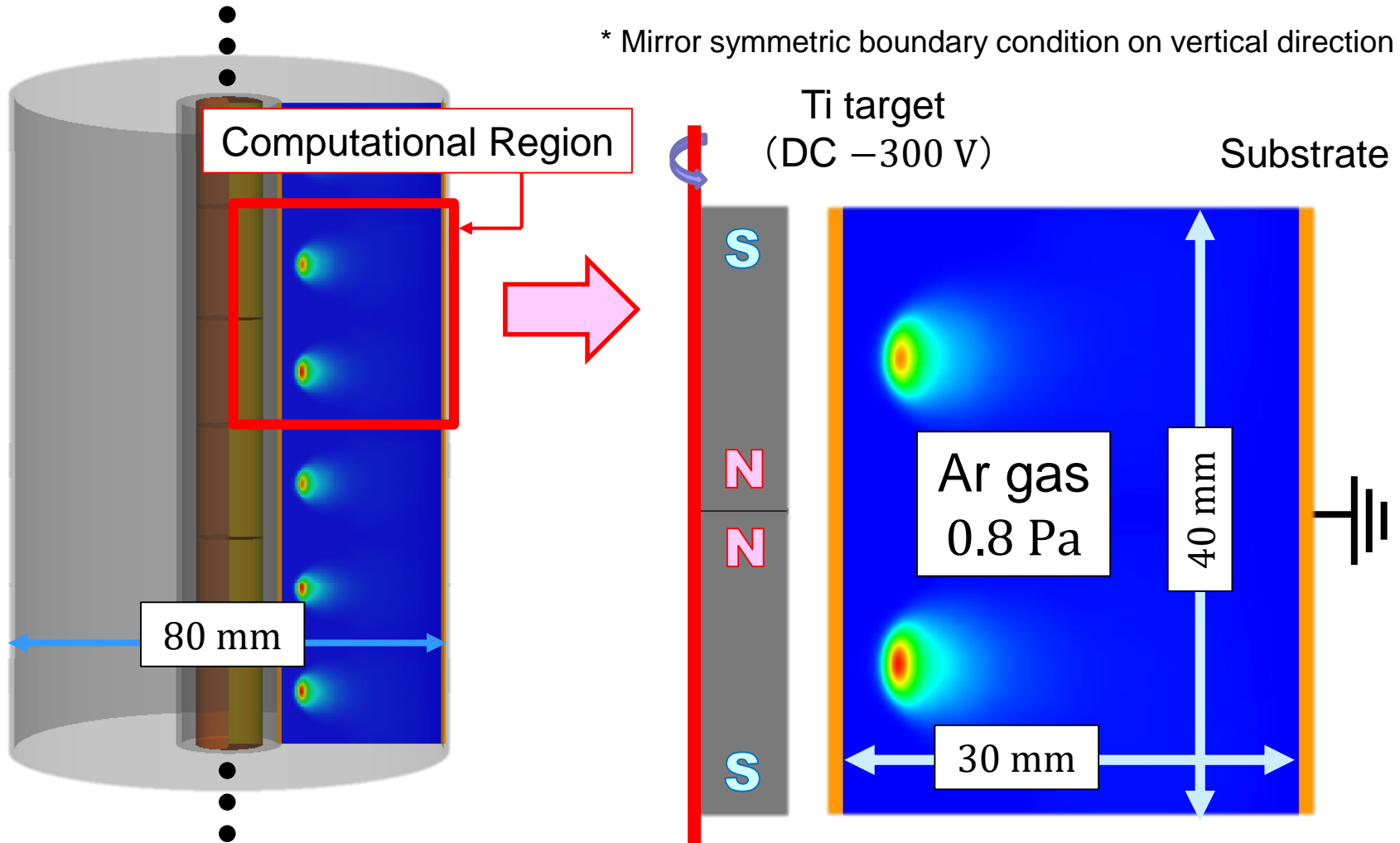
# Model

## Magnetron Sputtering for Cylindrical Target

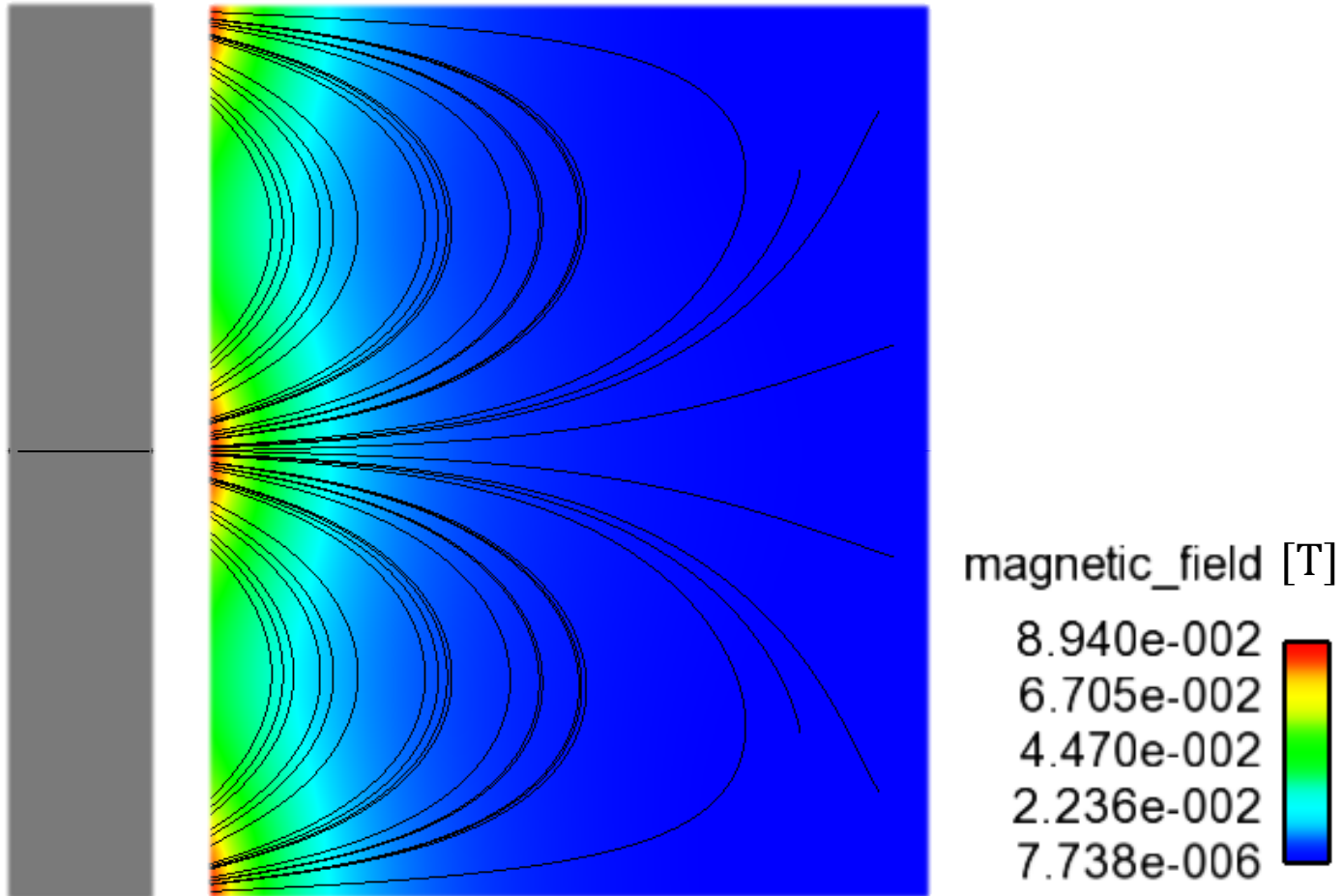
Ti coating of inner wall of 80 mm pipe

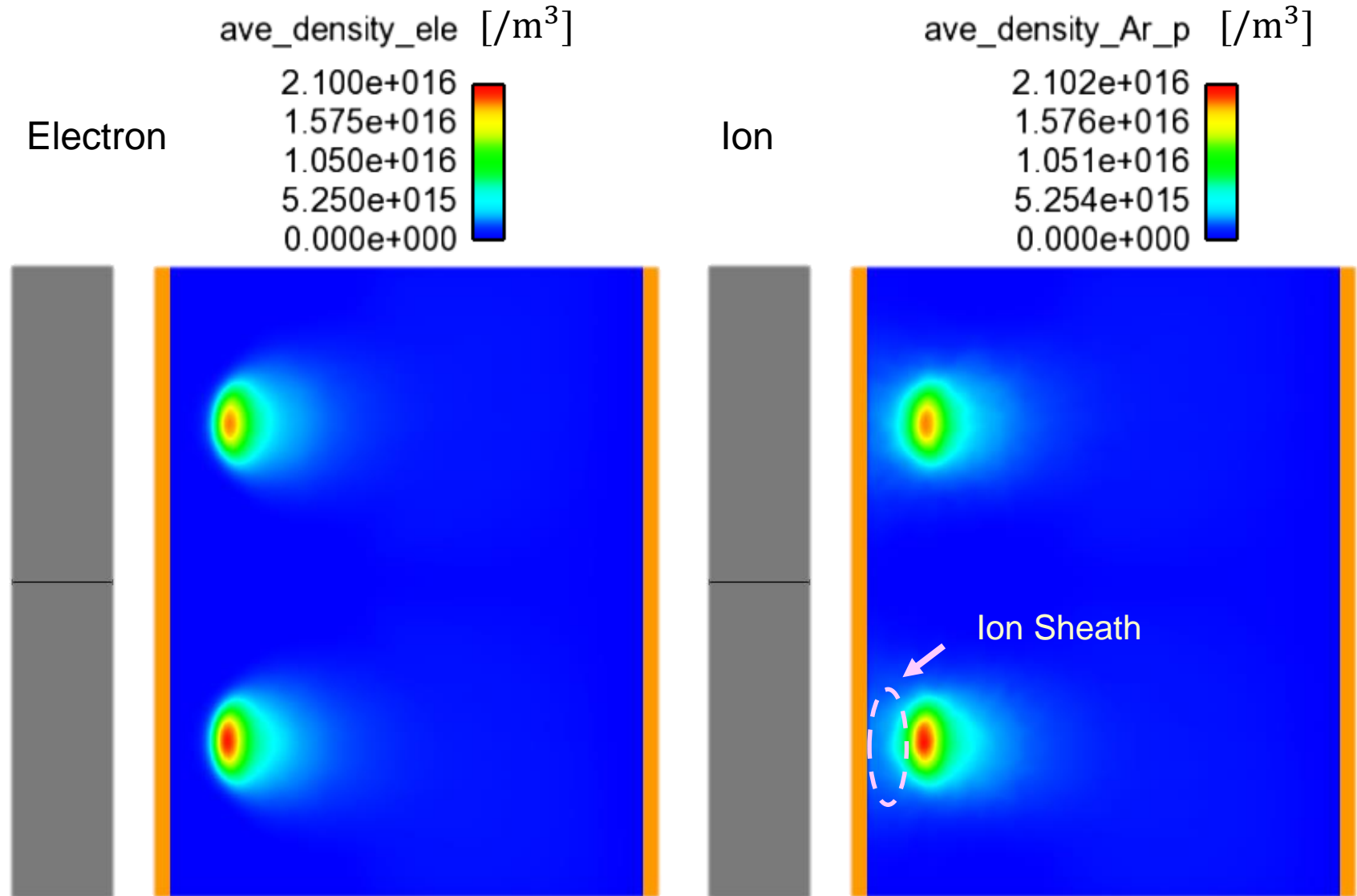
Axi-symmetric model

\* Mirror symmetric boundary condition on vertical direction



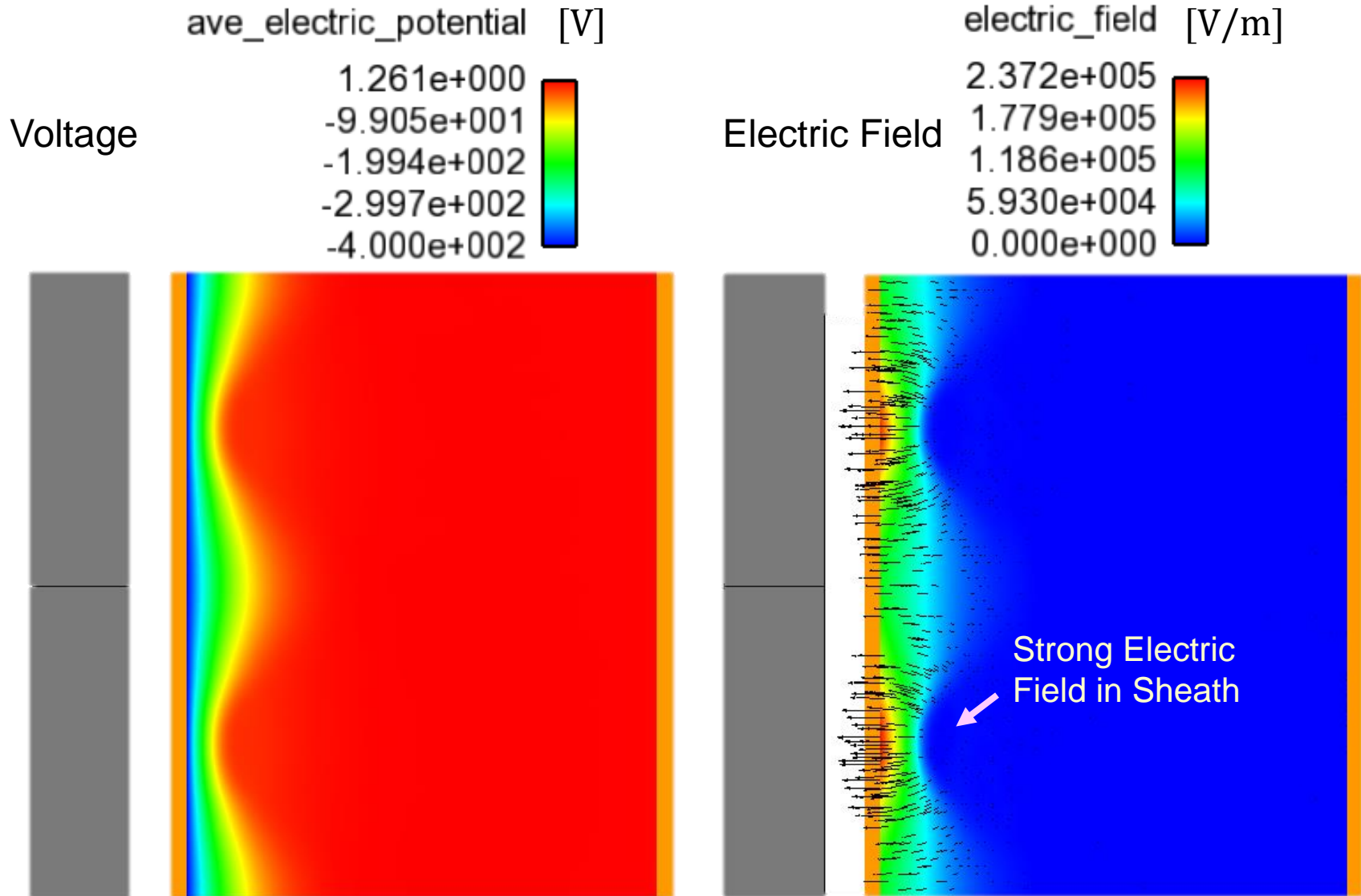
\* Solid line denotes magnetic flux





# Voltage/Electric Field

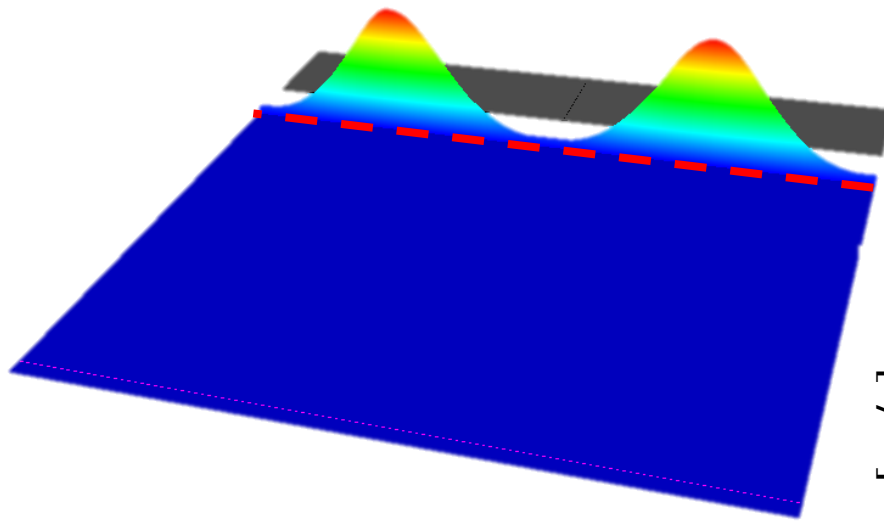
## Magnetron Sputtering for Cylindrical Target



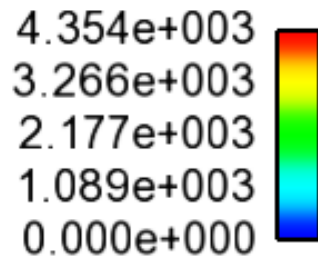
# Sputtering

## Magnetron Sputtering for Cylindrical Target

Ion Energy Flux on Target Surface



ave\_flux\_energy\_Ar\_p [W/m<sup>2</sup>]

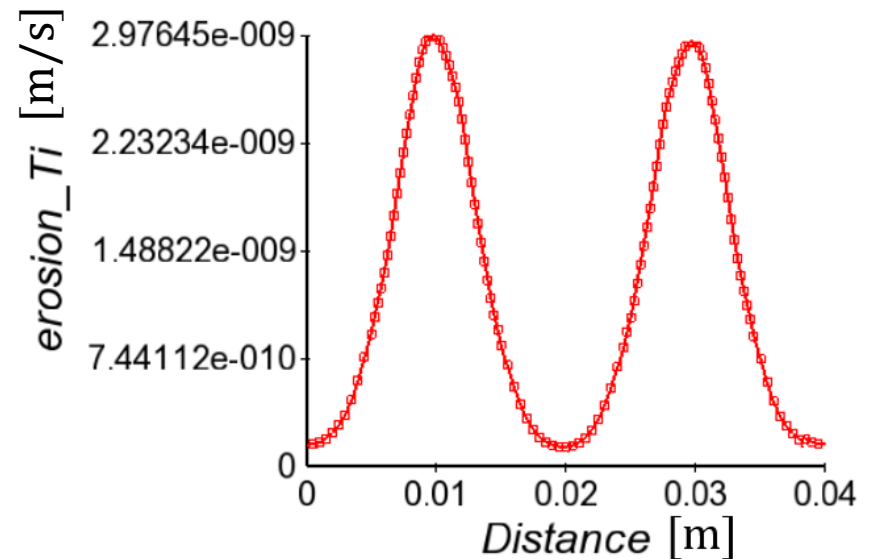


(On Target)

Current ~ 5.5 A/m<sup>2</sup>

Power ~ 2.2 kW/m<sup>2</sup>

Erosion Rate of Ti on Target Surface



# Deposition

## Magnetron Sputtering for Cylindrical Target

Density of Sputtered Particle

density\_Ti [ $/m^3$ ]

8.146e+016  
6.110e+016  
4.073e+016  
2.037e+016  
0.000e+000

